Substitute for form 1449/PTO	**Complete if Known**	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT *(Use as many sheets as necessary)*	Application Number	10/596,626-Conf. #8534
	Filing Date	June 19, 2006
	First Named Inventor	Karl-Heinz Schuster
	Art Unit	N/A
	Examiner Name	Not Yet Assigned
Sheet	1	of	1	Attorney Docket Number	01641/0204258-US0

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Examiner Initials*	Cite No.[1]	Document Number Number-Kind Code[2] (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
	AA*	US-6,717,722	04-06-2004	Shafer et al.	
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	BA	WO-2004/019128	03-04-2004	Nikon Corporation		√
	BB	WO-2005/081067	09-01-2005	CARL ZEISS SMT AG		√
	BC	WO-2005/106589	11-10-2005	CARL ZEISS SMT AG		√
	BD	EP-0 475 020-A	03-18-1992	International Business Machines Corporation		√
	BE	WO-2005/059654	06-30-2005	Carl Zeiss SMT AG		√

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NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.[1]	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T[2]
	CA	Smith, B. W. et al., "Water Immersion Optical Lithography for the 45nm Node", *Optical Microlithography XVI, Proceedings of SPIE* (2003) Vol. 5040; 679-689	
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	CC	Burnett, J.H. et al., " High Index Materials for 193 nm and 157 nm Immersion Lithography", International Symposium on Immersion & 157 nm Lithography, Vancouver, 8/2/2004	

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